

AMENDMENTS TO THE SPECIFICATION

Please replace the second full paragraph at page 32 of the specification with the following amended paragraph:

Fig. 4 ~~sows~~ shows the composition profile of silicon, oxygen and carbon in the direction of depth of the film relying upon the method of analyzing the composition in the vapor deposited film that is obtained. In the composition profile of Fig. 4, the sum of concentrations of silicon and oxygen is shown in Fig. 5 as Si + O. Further, the bonding energy of silicon in Fig. 5 is shown in Fig. 6.